74 (NEW) A polishing apparatus according to claim 73, wherein said polishing pressure comprises a fluid pressure.

75.(NEW) A polishing apparatus according to claim 73, wherein said polishing pressure comprises a compressed air pressure.

76.(NEW) A polishing apparatus comprising to claim 73, wherein said central area and said outer circumferential area are formed by chambers formed in said top ring.

45 (NEW)

A polishing apparatus according to claim 73, further comprising:

a third area located between said central area and said outer

circumferential area.

78.(NEW)

A polishing apparatus according to claim 73, further comprising:

a presser ring disposed around the workpiece and contacting a

polishing surface for polishing the workpiece.

79.(NEW)

A polishing apparatus according to claim 78, wherein said presser ring

is pressed by pressurized fluid.

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80.(NEW) A method for polishing a workpiece, comprising:

holding a workpiece on a surface of a top ring; and

applying a polishing pressure on a surface of the workpiece, wherein an area where said polishing pressure is applied is divided to a central area and an outer circumferential area of the workpiece, and the radial width of said outer circumferential area is narrower than that of said central area.

1

A method according to claim 80, wherein said polishing pressure comprises a fluid pressure.

<u>S2.(NEW)</u> A method according to claim 80, wherein said polishing pressure comprises a compressed air pressure.

outer circumferential area are formed by chambers formed in said top ring.

polishing pressure is applied is divided to said central area, said outer circumferential area and a third area located between said central area and said outer circumferential area.

85.(NEW) A method according to claim 80, further comprising:

pressing a presser ring disposed around the workpiece against a polishing surface for polishing the workpiece.

86.(NEW) A method according to claim 85, wherein said presser ring is pressed by pressurized fluid.

END

87.(NEW) A polishing apparatus for polishing a surface of a workpiece,

comprising:

a turntable having a polishing surface thereon;

a top ring to support the workpiece to be polished on a holding surface

of said top ring;

a presser ring vertically movably disposed around said top ring:

a mechanism to move said top ring vertically so that said top ring moves toward and away from said polishing surface;

a pressing mechanism to provide a first pressing force onto the workpiece, said first pressing force being different in a central portion and an outer circumferential portion of the workpiece; and

a pressing device to press said presser ring against said polishing surface under a second pressing force, said second pressing force being independently controllable with respect to said first pressing force.

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